



Elettra Sincrotrone Trieste

Deep X-Ray Lithography

E lettra Sincrotrone Trieste is a multidisciplinary European institute for research based in North East of Italy, specialized in the analysis of matter. Elettra offers also the possibility

to perform X - Ray Lithography for the fabrication of micro and nanodevices.

Deep X-Ray Lithography (DXRL) is a manufacturing process by which a material, which changes its dissolution rate in a liquid solvent (developer) under high energy irradiation, is exposed through an X-ray mask to synchrotron radiation.

The pattern of the mask is transferred to the material. This is possible by the availability of synchrotron radiation characterized by high resolution, high intensity and extreme parallelism.

2. Development

uld cavity

40 XB 27.0









Absorber

1. Irradiation

radiatic



http://www.elettra.trieste.it/elettra-beamlines/dxrl.html http://www.elettra.trieste.it/ILO/

Microsctructures have been obtained with high spatial resolution (200nm for a wall thickness of 100 μ m), high aspect ratios (up to 40), great structural heights (up to 3mm) and parallel edges.

140 µm



Deep X-Ray Lithography Applications



50 µm

Marmiroli et al. NIMB 2010







MEMS

- Microgears
- Microturbines
- Microgenerators

MICROFLUIDICS

- Drug delivery system
- Micro gearpumps
- Microneedles
- •Lab on chip

MICRO OPTICS

- Difractive lenses
- •Optical micro prisms

FABRICATION TOOLS

•Electro Discharge Machine Electrodes



5.0kV X750 10µm 120400





200 µm

Marmiroli et al. LOC 2009

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